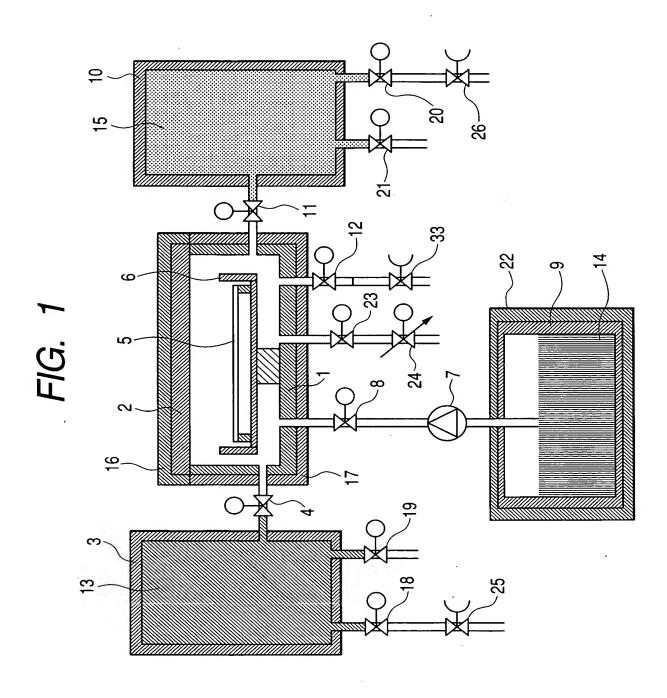
App No.: Not Yet Assigned Docket No.: N9460.0018/Pelnventor: Hisayuki Takasu, et al.
Title: A METHOD OF DEVELOPING A RESIST FILM AND A RESIST DEVELOPMENT PROCESSOR

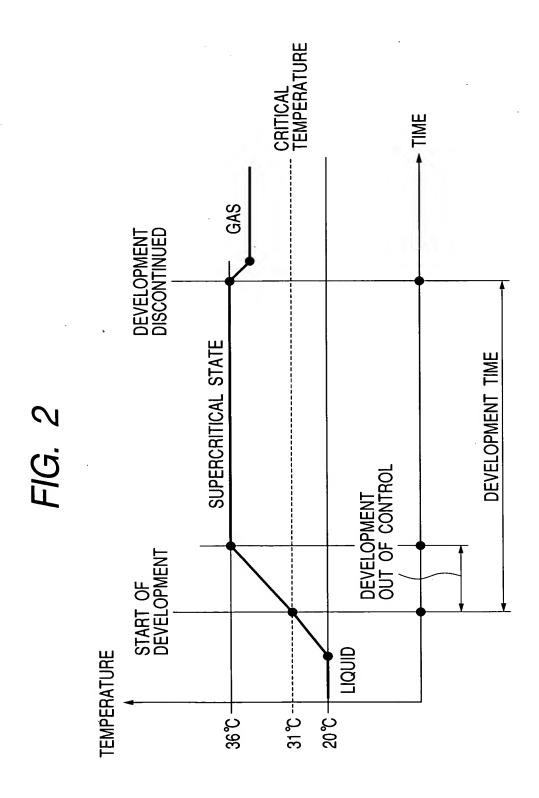
Docket No.: N9460.0018/P018

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Title: A METHOD OF DEVELOPING A RESIST FILM AND A RESIST DEVELOPMENT PROCESSOR

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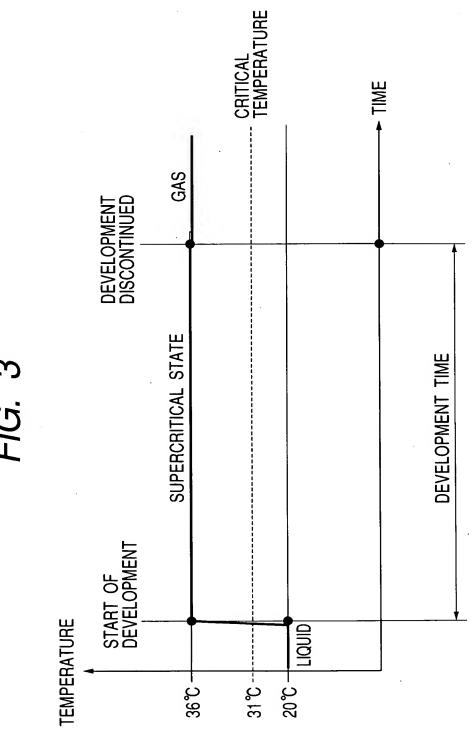


Docket No.: N9460.0018/P018 App No.: Not Yet Assigned Inventor: Hisayuki Takasu, et al. Title: A METHOD OF DEVELOPING A RESIST FILM AND A

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RESIST DEVELOPMENT PROCESSOR



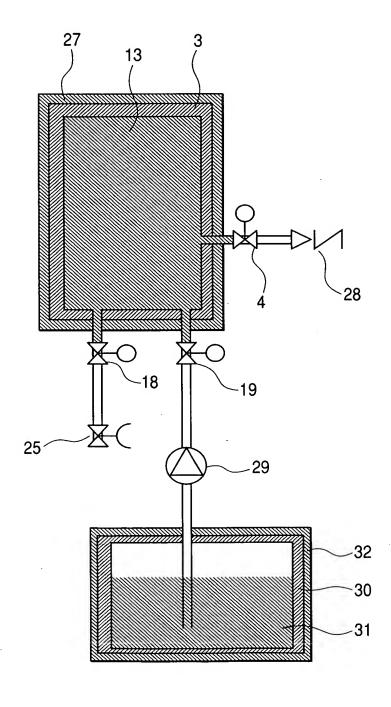
App No.: Not Yet Assigned Docket No.: N9460.0018/Poinventor: Hisayuki Takasu, et al.

Title: A METHOD OF DEVELOPING A RESIST FILM AND A RESIST DEVELOPMENT PROCESSOR

Docket No.: N9460.0018/P018

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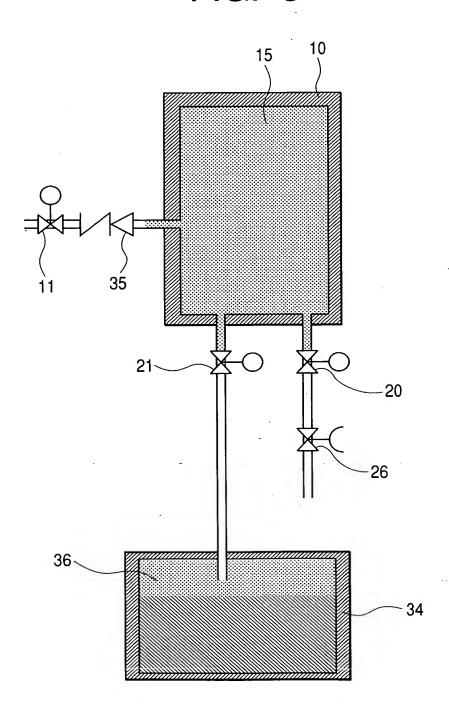
FIG. 4



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FIG. 5



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RESIST DEVELOPMENT PROCESSOR

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FIG. 6

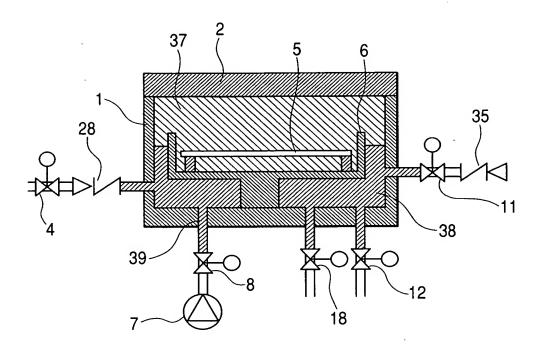


FIG. 7

